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**Information Disclosure Statement By Applicant** 

(Use Several Sheets if Necessary)

Atty Docket No.

NOVLP096/NVLS-2902

Applicant:

Wongsenakhum et al. Filing Date March 31, 2004

Application No.:

10/815,560

Group 2823

**U.S. Patent Documents** 

Examiner						Sub-	Filing
Initial/	No.	Patent No.	Date	Patentee	Class_	class	Date
111/2	A1	5,956,609	09.1999	Lee et al.			<u> </u>
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Foreign Patent or Published Foreign Patent Application

Examiner		Document	Publication	Country or		Sub-	Transl	lation
Initial	No.	No.	Date	Patent Office	Class	class	Yes	No
			<u> </u>					1

## **Other Documents**

		Other 200111111				
Examiner						
Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication				
:	C1	Chan et al., "Methods for Growing Low-Resistivity Tungsten Film", Novellus				
gnz,		Systems, Inc., filed November 1, 2005, Application No. 11/265,531, pages 1-35. [NOVLP137/NVLS-0003093]				
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( n/d),		December 16, 2005, Application No. 11/305,368, pages 1-39.				
		[NOVLP063D1/NVLS-2615D1].				
and	C3	U.S. Office Action mailed December 28, 2005, from U.S. Application No. 10/649,351 [NOVLP033X1/NVLS-000498X1].				
- ANTO		10/042,331 [NOVEL 0332/1/NVES-00042021].				
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Examiner /d	1 -	Date Considered				

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Form 1449 (Modified)

**Information Disclosure Statement By Applicant** 

(Use Several Sheets if Necessary)

Atty Docket No. NOVLP096/NVLS-2902

Applicant:

Wongsenakhum et al.

Filing Date March 31, 2004 Application No.:

10/815,560

Group 2823

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Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub- class	Filing Date
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Foreign Patent or Published Foreign Patent Application

Examiner		Document	Publication	Country or		Sub-	Trans	lation
Initial	No.	No.	Date	Patent Office	Class	class	Yes	No

## **Other Documents**

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Mg	Cl	Vongsenakhum et al., "Reducing Silicon Attack and Improving Resistivity of ungsten Nitride Film", Novellus Systems, Inc., filed February 6, 2006, Application o. Not yet assigned, pages 1-26. [NOVLP138/NVLS-3094]				
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Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.